

Interference Search

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L31	1324	((resist or photoresist) same (ash\$6 or remov\$6 or incinerat\$6 or strip\$6) same plasma).clm.	US-PGPUB; USPAT	OR	ON	2005/12/05 16:19
L32	47368	((nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3 or (form\$6 adj gas)) near20 (flow or flowrate or sccm or ratio or percent\$6 or concentrat\$6 or volume or "%"))).clm.	US-PGPUB; USPAT	OR	ON	2005/12/05 16:19
L33	32107	((O2 or oxygen or O?sub\$3) near20 (flow or flowrate or sccm or ratio or concentrat\$6 or percent\$6 or "%" or volume)).clm.	US-PGPUB; USPAT	OR	ON	2005/12/05 16:20
L34	80	31 and 32 and 33	US-PGPUB; USPAT	OR	ON	2005/12/05 16:20
L35	3	34 and (HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid)).clm.	US-PGPUB; USPAT	OR	ON	2005/12/05 16:21

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	24305	(resist or photoresist) same (ash\$6 or remov\$6 or incinerat\$6) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 12:49
L2	16508	1 and ((dielectric or SiC or silicate or IMD or IML or IDM or IDL or glass or carbide or SiO2 or SiO?sub\$3 or PSG or BSG or BPSG or USG or hole or viahole or contacthole) same (pattern\$6 or etch\$6 or mask\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 12:51
L3	5235	2 and (HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 12:52
L4	4969	3 and (@ad<"20031201" or @rlad<="20031201")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 12:53
L5	3863	4 and (nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3 or (form\$6 adj gas))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:09
L9	1185	5 and ((O2 or oxygen or O?sub\$3) near20 (flow or flowrate or sccm or ratio or concentrat\$6 or percent\$6 or "%" or volume))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:10
L10	1591	5 and ((nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3 or (form\$6 adj gas)) near20 (flow or flowrate or sccm or ratio or percent\$6 or concentrat\$6 or volume or "%"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:04
L11	870	10 and 9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:04
L12	849	11 and (temperature or degree or celcius)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:06

L13	823	12 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:06
L14	4373	1 same (nitrogen or N ₂ or hydrogen or H ₂ or N ₂ or H ₂ or (form\$6 adj gas))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:09
L15	10725	1 same (O ₂ or oxygen or O ₂)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:10
L16	269	13 and 14 and 15	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:10

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	24305	(resist or photoresist) same (ash\$6 or remov\$6 or incinerat\$6) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 15:59
L2	16508	1 and ((dielectric or SiC or silicate or IMD or IML or IDM or IDL or glass or carbide or SiO2 or SiO?sub\$3 or PSG or BSG or BPSG or USG or hole or viahole or contacthole) same (pattern\$6 or etch\$6 or mask\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L3	5235	2 and (HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L4	4969	3 and (@ad<"20031201" or @rlad<="20031201")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L5	3863	4 and (nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3 or (form\$6 adj gas))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:09
L9	1185	5 and ((O2 or oxygen or O?sub\$3) near20 (flow or flowrate or sccm or ratio or concentrat\$6 or percent\$6 or "%" or volume))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:01
L10	1591	5 and ((nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3 or (form\$6 adj gas)) near20 (flow or flowrate or sccm or ratio or percent\$6 or concentrat\$6 or volume or "%"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:04
L11	870	10 and 9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:04
L12	849	11 and (temperature or degree or celcius)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:06

L13	823	12 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:06
L14	4373	1 same (nitrogen or N ₂ or hydrogen or H ₂ or N ₂ or H ₂ or (form\$6 adj gas))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:09
L15	10725	1 same (O ₂ or oxygen or O ₂)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 13:10
L16	269	13 and 14 and 15	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:03
L23	6703	(resist or photoresist) same strip\$6 same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 15:59
L24	4927	23 and ((dielectric or SiC or silicate or IMD or IML or IDM or IDL or glass or carbide or SiO ₂ or SiO ₂ or PSG or BSG or BPSG or USG or hole or viahole or contacthole) same (pattern\$6 or etch\$6 or mask\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L25	1727	24 and (HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L26	1655	25 and (@ad<"20031201" or @rlad<="20031201")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:00
L27	517	26 and ((nitrogen or N ₂ or hydrogen or H ₂ or N ₂ or H ₂ or (form\$6 adj gas)) near20 (flow or flowrate or sccm or ratio or percent\$6 or concentrat\$6 or volume or "%"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:01

L28	393	26 and ((O2 or oxygen or O ₂) near 20 (flow or flowrate or sccm or ratio or concentration or percent or "%" or volume))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:02
L29	278	27 and 28	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:02
L30	146	29 not 16	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/05 16:03